

Focus Tech DY-6600

Developer Concentrate

Product Description

DV-6600 is a highly concentrated developer solution designed for use in photoresist and soldermask developing processes. Formulated using water softening agents, working solutions of DV-6600 can be made using tap water with up to 400 ppm's of dissolved solids without forming significant hardness scale. DV-6600 also contains cleaning compounds that help break up resist residues to prevent deposition and build up in process and control equipment. The Focus Tech developing system combines high quality with ease of use to provide a superior developing system.

Features		Benefits
Highly concentrated Alignment of the second se		Minimizes handling
Softening agents		Iliminates need for purified water
Detergent additives		Extends uptime by slowing scum build-up
Physical Properties		
Concentration: Specific gravity: pH:	600 g/L as potassium carbonate 1.40 >12	

Operating Parameters

Make Up: Replenishment:

Process pH: Temperature:

Appearance:

Freezing point:

1.33 - 1.67% v/v DV-6600, 8 – 10 g/L as potassium carbonate 1.33 - 1.67% v/v DV-6600 8 – 10 g/L as potassium carbonate 10.4 – 10.8 80 $^\circ F$ – 90 $^\circ F$

Storage

Store in original containers above 40 °F.

clear, water white

<40 °F

Safety

CAUTION! DV-6600 concentrates and working solutions contain strong alkaline ingredients. Avoid contact with eyes, skin and clothing. Wear chemical handler's gloves, goggles and protective clothing when handling. Read and understand Material Safety Data Sheet before using this product.

Notice

The information and recommendations, contained herein, regarding this product are, to the best of our knowledge, true and accurate. We make no guarantee of results because the conditions of actual use are beyond our control. We assume no liability for damages or penalties resulting from the use of this product or following our recommendations. Our recommendations and suggestions for use of this product are not intended to grant license to operate under or infringe any patent.